

IN THE CLAIMS

1. (Original) A stencil mask comprising:
a membrane forming thin layer comprising:
membrane areas, each membrane area including a plurality of pattern areas in which a plurality of apertures that allow permeation of particle beams is formed, and a plurality of non-pattern areas placed between the plurality of pattern areas; and
a border area which limits the membrane areas;
a main strut formed on the border area of the membrane forming thin layer to support the membrane areas; and
an auxiliary strut formed on the non-pattern areas inside the membrane areas, the auxiliary strut dividing the membrane areas into a plurality of divided membrane areas and supporting each divided membrane area.
2. (Original) The stencil mask of claim 1, wherein the auxiliary strut penetrates the membrane forming thin layer.
3. (Currently amended) The stencil mask of claim 1, wherein the membrane forming thin layer comprises a first side opposing the main strut and a second side opposite the first side, and the auxiliary strut has a surface exposed through the second side.
4. (Original) The stencil mask of claim 1, wherein the auxiliary strut extends by a first length from the first side of the membrane forming thin layer and the first length is shorter than a length of the main strut.
5. (Original) The stencil mask of claim 1, wherein the auxiliary strut overlaps the border area and the main strut.

6. (Original) The stencil mask of claim 1, wherein the membrane forming thin layer is made of a silicon layer and the auxiliary strut is made of a material selected from the group consisting of a polysilicon layer, a TiN layer, a Ti layer, and a combination layer made of two or more of these three materials.

7. (Original) The stencil mask of claim 1, further comprising a protection layer partially covering the auxiliary strut.

8. (Original) The stencil mask of claim 7, wherein the membrane forming thin layer comprises a first side opposing the main strut and a second side opposite the first side, the second side of the membrane forming thin layer exposes a first surface of the auxiliary strut, and the protection layer does not cover the first surface of the auxiliary strut.

9. (Original) The stencil mask of claim 7, wherein the protection layer is made of a material selected from the group consisting of a Ti layer, a TiN layer, a silicon nitride layer, and a combination layer made of two or more of these three materials.

10. (Original) The stencil mask of claim 1, further comprising an oxide layer interposed between the border area of the membrane forming thin layer and the main strut.

11. (Original) The stencil mask of claim 1, wherein the auxiliary strut has a solid cross section and a columnar shape.

12. (Original) The stencil mask of claim 1, wherein the membrane forming thin layer has a first side facing the main strut and a second side partially exposing a first surface of the auxiliary strut, and part of the first surface is recessed such that the auxiliary strut has a "U" shape.

13. (Original) The stencil mask of claim 1, wherein the auxiliary strut is located in the non-pattern areas of the membrane forming thin layer such that the membrane areas are divided into a plurality of divided membrane areas sectioned by a cellblock unit.

14-49. (Canceled)

50. (Original) A stencil mask comprising:

a membrane forming thin layer having membrane areas and a border area that limits the membrane areas;

a main strut formed on the border area of the membrane forming thin layer that supports the membrane areas; and

an auxiliary strut formed inside the membrane areas that divides the membrane areas into a plurality of divided membrane areas and supports the plurality of divided membrane areas.

51. (Original) The stencil mask of claim 50, further comprising a plurality of apertures formed in the membrane areas.